

Supplementary Information

Strain- and chirality-engineered tunability of electronic and thermoelectric properties in SiC nanotubes: insights from first-principles calculations

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Optimized crystal structure of (10,0) SiCNT (CIF format)

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_cell_length_c             5.375500
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_cell_angle_beta          90.000000
_cell_angle_gamma         120.000000
_cell_volume               816.843149
_space_group_name_H-M_alt  'P 1'
_space_group_IT_number     1

loop_
_space_group_symop_operation_xyz
  'x, y, z'

loop_
_atom_site_label
_atom_site_occupancy
_atom_site_fract_x
_atom_site_fract_y
_atom_site_fract_z
_atom_site_adp_type
_atom_site_U_iso_or_equiv
_atom_site_type_symbol
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C	1.0	0.873700	0.500000	0.333000	Uiso ? C
Si	1.0	0.873700	0.500000	0.000000	Uiso ? Si
C	1.0	0.922000	0.633300	0.833000	Uiso ? C
Si	1.0	0.922000	0.633300	0.500000	Uiso ? Si
C	1.0	0.929100	0.753600	0.333000	Uiso ? C
Si	1.0	0.929100	0.753600	0.000000	Uiso ? Si
C	1.0	0.894200	0.849100	0.833000	Uiso ? C
Si	1.0	0.894200	0.849100	0.500000	Uiso ? Si
C	1.0	0.820600	0.910400	0.333000	Uiso ? C
Si	1.0	0.820600	0.910400	0.000000	Uiso ? Si
C	1.0	0.715700	0.931500	0.833000	Uiso ? C
Si	1.0	0.715700	0.931500	0.500000	Uiso ? Si
C	1.0	0.589700	0.910400	0.333000	Uiso ? C
Si	1.0	0.589700	0.910400	0.000000	Uiso ? Si
C	1.0	0.454900	0.849100	0.833000	Uiso ? C
Si	1.0	0.454900	0.849100	0.500000	Uiso ? Si
C	1.0	0.324500	0.753600	0.333000	Uiso ? C
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Si	1.0	0.211300	0.633300	0.500000	Uiso ? Si
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Si	1.0	0.078000	0.366700	0.500000	Uiso ? Si
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Si	1.0	0.070900	0.246400	0.000000	Uiso ? Si
C	1.0	0.105800	0.150900	0.833000	Uiso ? C
Si	1.0	0.105800	0.150900	0.500000	Uiso ? Si
C	1.0	0.179400	0.089600	0.333000	Uiso ? C
Si	1.0	0.179400	0.089600	0.000000	Uiso ? Si
C	1.0	0.284300	0.068500	0.833000	Uiso ? C

Si	1.0	0.284300	0.068500	0.500000	Uiso ? Si
C	1.0	0.410300	0.089600	0.333000	Uiso ? C
Si	1.0	0.410300	0.089600	0.000000	Uiso ? Si
C	1.0	0.545100	0.150900	0.833000	Uiso ? C
Si	1.0	0.545100	0.150900	0.500000	Uiso ? Si
C	1.0	0.675500	0.246400	0.333000	Uiso ? C
Si	1.0	0.675500	0.246400	0.000000	Uiso ? Si
C	1.0	0.788700	0.366700	0.833000	Uiso ? C
Si	1.0	0.788700	0.366700	0.500000	Uiso ? Si

Optimized crystal structure of (11,0) SiCNT (CIF format)

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CRYSTAL DATA

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data_VESTA_phase_1

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_cell_length_b 14.230400

_cell_length_c 5.374600

_cell_angle_alpha 90.000000

_cell_angle_beta 90.000000

_cell_angle_gamma 120.000000

_cell_volume 942.564318

_space_group_name_H-M_alt 'P 1'

_space_group_IT_number 1

loop_

_space_group_symop_operation_xyz

'x, y, z'

loop_

_atom_site_label

_atom_site_occupancy

_atom_site_fract_x

_atom_site_fract_y

_atom_site_fract_z

_atom_site_adp_type

_atom_site_U_iso_or_equiv

_atom_site_type_symbol

C	1.0	0.882400	0.500000	0.333100	Uiso ? C
Si	1.0	0.882400	0.500000	0.000000	Uiso ? Si
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Si	1.0	0.929100	0.624400	0.500000	Uiso ? Si
C	1.0	0.941100	0.738700	0.333100	Uiso ? C
Si	1.0	0.941100	0.738700	0.000000	Uiso ? Si
C	1.0	0.917300	0.833700	0.833100	Uiso ? C
Si	1.0	0.917300	0.833700	0.500000	Uiso ? Si
C	1.0	0.859700	0.901700	0.333100	Uiso ? C
Si	1.0	0.859700	0.901700	0.000000	Uiso ? Si
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Si	1.0	0.773000	0.937100	0.500000	Uiso ? Si
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Si	1.0	0.542000	0.901700	0.500000	Uiso ? Si
C	1.0	0.416400	0.833700	0.333100	Uiso ? C
Si	1.0	0.416400	0.833700	0.000000	Uiso ? Si
C	1.0	0.297700	0.738700	0.833100	Uiso ? C

Si	1.0	0.297700	0.738700	0.500000	Uiso ? Si
C	1.0	0.195300	0.624400	0.333100	Uiso ? C
Si	1.0	0.195300	0.624400	0.000000	Uiso ? Si
C	1.0	0.117600	0.500000	0.833100	Uiso ? C
Si	1.0	0.117600	0.500000	0.500000	Uiso ? Si
C	1.0	0.070900	0.375600	0.333100	Uiso ? C
Si	1.0	0.070900	0.375600	0.000000	Uiso ? Si
C	1.0	0.058900	0.261300	0.833100	Uiso ? C
Si	1.0	0.058900	0.261300	0.500000	Uiso ? Si
C	1.0	0.082700	0.166300	0.333100	Uiso ? C
Si	1.0	0.082700	0.166300	0.000000	Uiso ? Si
C	1.0	0.140300	0.098300	0.833100	Uiso ? C
Si	1.0	0.140300	0.098300	0.500000	Uiso ? Si
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Si	1.0	0.227000	0.062900	0.000000	Uiso ? Si
C	1.0	0.335900	0.062900	0.833100	Uiso ? C
Si	1.0	0.335900	0.062900	0.500000	Uiso ? Si
C	1.0	0.458000	0.098300	0.333100	Uiso ? C
Si	1.0	0.458000	0.098300	0.000000	Uiso ? Si
C	1.0	0.583600	0.166300	0.833100	Uiso ? C
Si	1.0	0.583600	0.166300	0.500000	Uiso ? Si
C	1.0	0.702300	0.261300	0.333100	Uiso ? C
Si	1.0	0.702300	0.261300	0.000000	Uiso ? Si
C	1.0	0.804700	0.375600	0.833100	Uiso ? C
Si	1.0	0.804700	0.375600	0.500000	Uiso ? Si

Optimized crystal structure of (6,0) SiCNT (CIF format)

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_cell_angle_alpha          90.000000
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_cell_angle_gamma          120.000000
_cell_volume                405.047361
_space_group_name_H-M_alt   'P 1'
_space_group_IT_number      1

loop_
_space_group_symop_operation_xyz
  'x, y, z'

loop_
  _atom_site_label
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  _atom_site_adp_type
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C	1.0	0.820400	0.500000	0.332400	Uiso ? C
Si	1.0	0.820400	0.500000	0.000000	Uiso ? Si
C	1.0	0.870000	0.685000	0.832400	Uiso ? C
Si	1.0	0.870000	0.685000	0.500000	Uiso ? Si
C	1.0	0.820400	0.820400	0.332400	Uiso ? C
Si	1.0	0.820400	0.820400	0.000000	Uiso ? Si
C	1.0	0.685000	0.870000	0.832400	Uiso ? C
Si	1.0	0.685000	0.870000	0.500000	Uiso ? Si
C	1.0	0.500000	0.820400	0.332400	Uiso ? C
Si	1.0	0.500000	0.820400	0.000000	Uiso ? Si
C	1.0	0.315000	0.685000	0.832400	Uiso ? C
Si	1.0	0.315000	0.685000	0.500000	Uiso ? Si
C	1.0	0.179600	0.500000	0.332400	Uiso ? C
Si	1.0	0.179600	0.500000	0.000000	Uiso ? Si
C	1.0	0.130000	0.315000	0.832400	Uiso ? C
Si	1.0	0.130000	0.315000	0.500000	Uiso ? Si
C	1.0	0.179600	0.179600	0.332400	Uiso ? C
Si	1.0	0.179600	0.179600	0.000000	Uiso ? Si
C	1.0	0.315000	0.130000	0.832400	Uiso ? C
Si	1.0	0.315000	0.130000	0.500000	Uiso ? Si
C	1.0	0.500000	0.179600	0.332400	Uiso ? C
Si	1.0	0.500000	0.179600	0.000000	Uiso ? Si
C	1.0	0.685000	0.315000	0.832400	Uiso ? C
Si	1.0	0.685000	0.315000	0.500000	Uiso ? Si

Optimized crystal structure of (6,6) SiCNT (CIF format)

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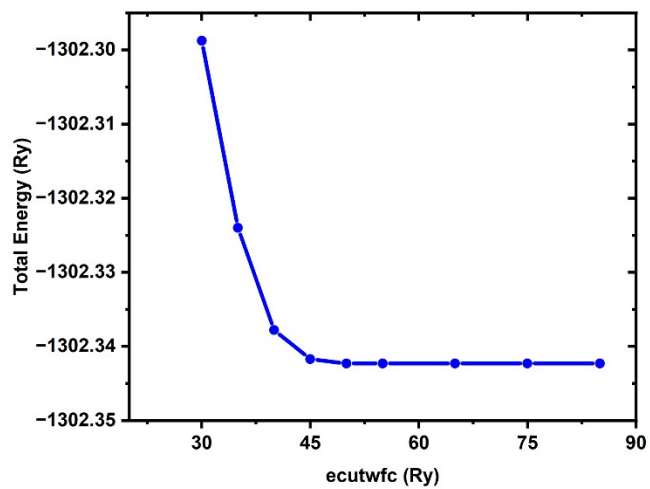
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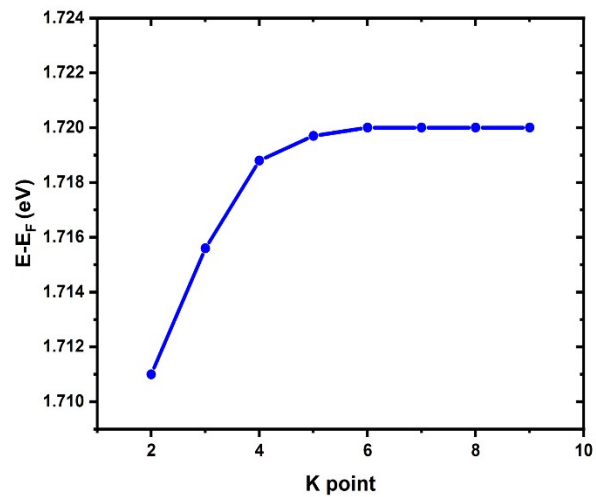
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 C 1.0 0.929100 0.649200 0.000000 Uiso ? C
 Si 1.0 0.935700 0.717800 0.500000 Uiso ? Si
 C 1.0 0.909300 0.833900 0.500000 Uiso ? C
 Si 1.0 0.877300 0.877300 0.000000 Uiso ? Si
 C 1.0 0.779900 0.929100 0.000000 Uiso ? C

Si	1.0	0.717800	0.935700	0.500000	Uiso ? Si
C	1.0	0.575400	0.909300	0.500000	Uiso ? C
Si	1.0	0.500000	0.877300	0.000000	Uiso ? Si
C	1.0	0.350800	0.779900	0.000000	Uiso ? C
Si	1.0	0.282200	0.717800	0.500000	Uiso ? Si
C	1.0	0.166100	0.575400	0.500000	Uiso ? C
Si	1.0	0.122700	0.500000	0.000000	Uiso ? Si
C	1.0	0.070900	0.350800	0.000000	Uiso ? C
Si	1.0	0.064300	0.282200	0.500000	Uiso ? Si
C	1.0	0.090700	0.166100	0.500000	Uiso ? C
Si	1.0	0.122700	0.122700	0.000000	Uiso ? Si
C	1.0	0.220100	0.070900	0.000000	Uiso ? C
Si	1.0	0.282200	0.064300	0.500000	Uiso ? Si
C	1.0	0.424600	0.090700	0.500000	Uiso ? C
Si	1.0	0.500000	0.122700	0.000000	Uiso ? Si
C	1.0	0.649200	0.220100	0.000000	Uiso ? C
Si	1.0	0.717800	0.282200	0.500000	Uiso ? Si
C	1.0	0.833900	0.424600	0.500000	Uiso ? C

Figure S1



(a) Cutoff energy convergence for (10,0) SiCNT



(b) k-point convergence of the bandgap for (10,0) SiCNT

Fig. S1. (a) Cutoff energy convergence for (10,0) SiCNT (b) k- point convergence of the bandgap for (10,0) SiCNT

Figure S2

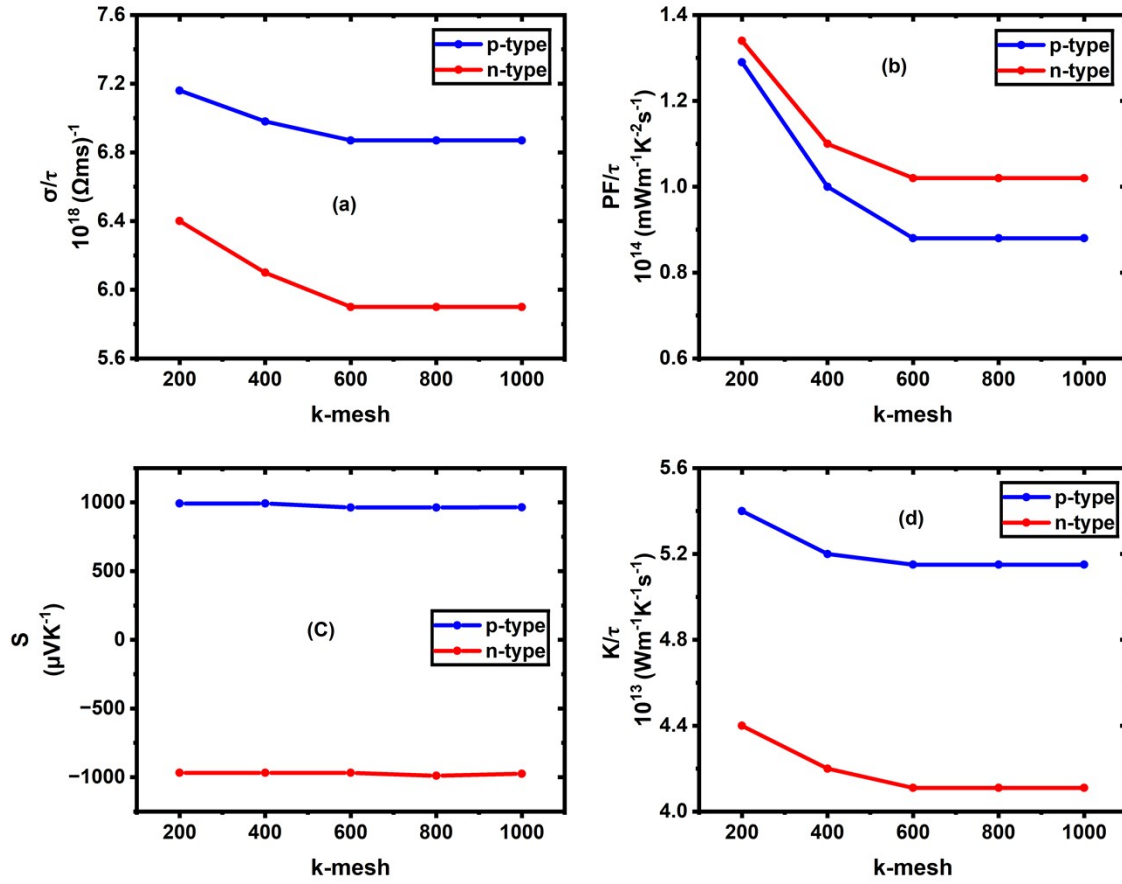


Fig. S2. k-mesh convergence of (a) electrical conductivity (σ/τ), (b) power factor (PF/τ), (c) Seebeck coefficient (S), and (d) electronic thermal conductivity (κ/τ) for the (6,0) SiCNT.

Figure S3

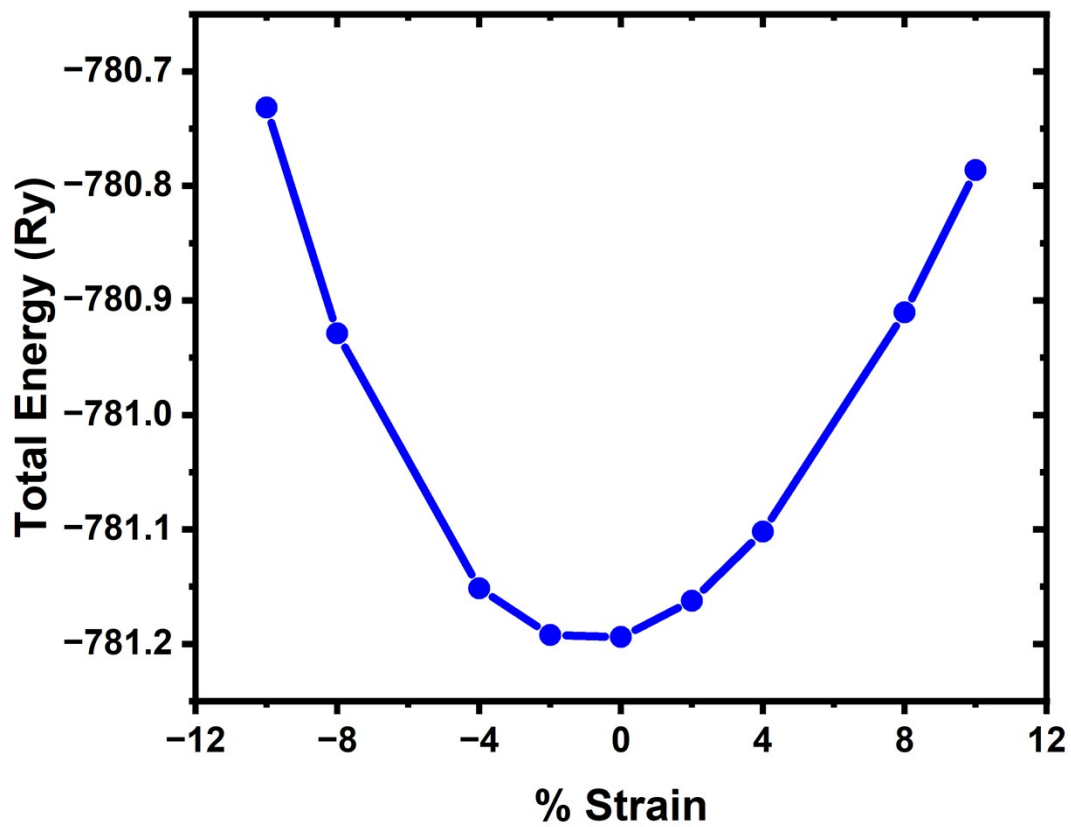


Fig. S3. Total energy as a function of applied uniaxial strain (-10% to +10%) for the (6,0) SiCNT

Figure S4

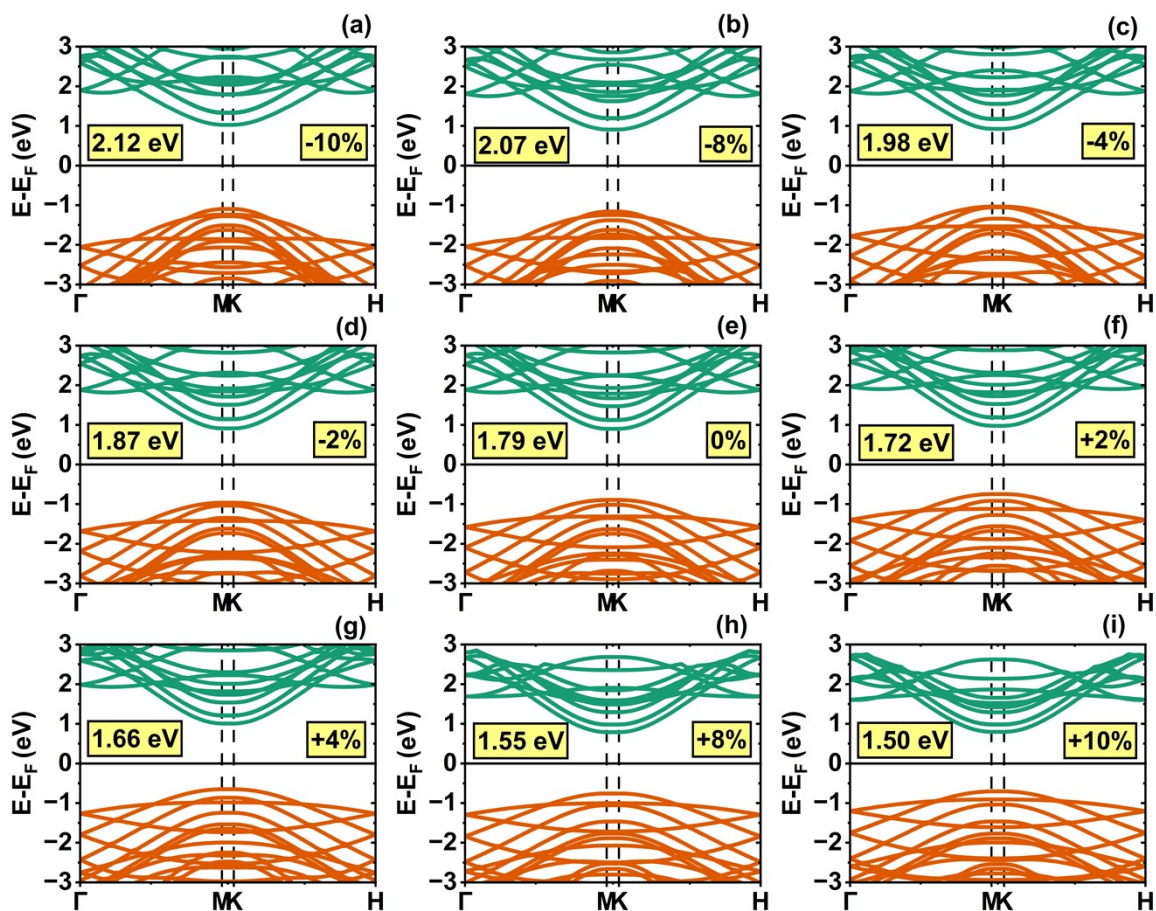


Fig. S4. Electronic band structures of the (11,0) single-walled SiCNT under uniaxial strain: (a) -10% , (b) -8% , (c) -4% , (d) -2% , (e) 0% (relaxed state), (f) $+2\%$, (g) $+4\%$, (h) $+8\%$, and (i) $+10\%$.

Figure S5

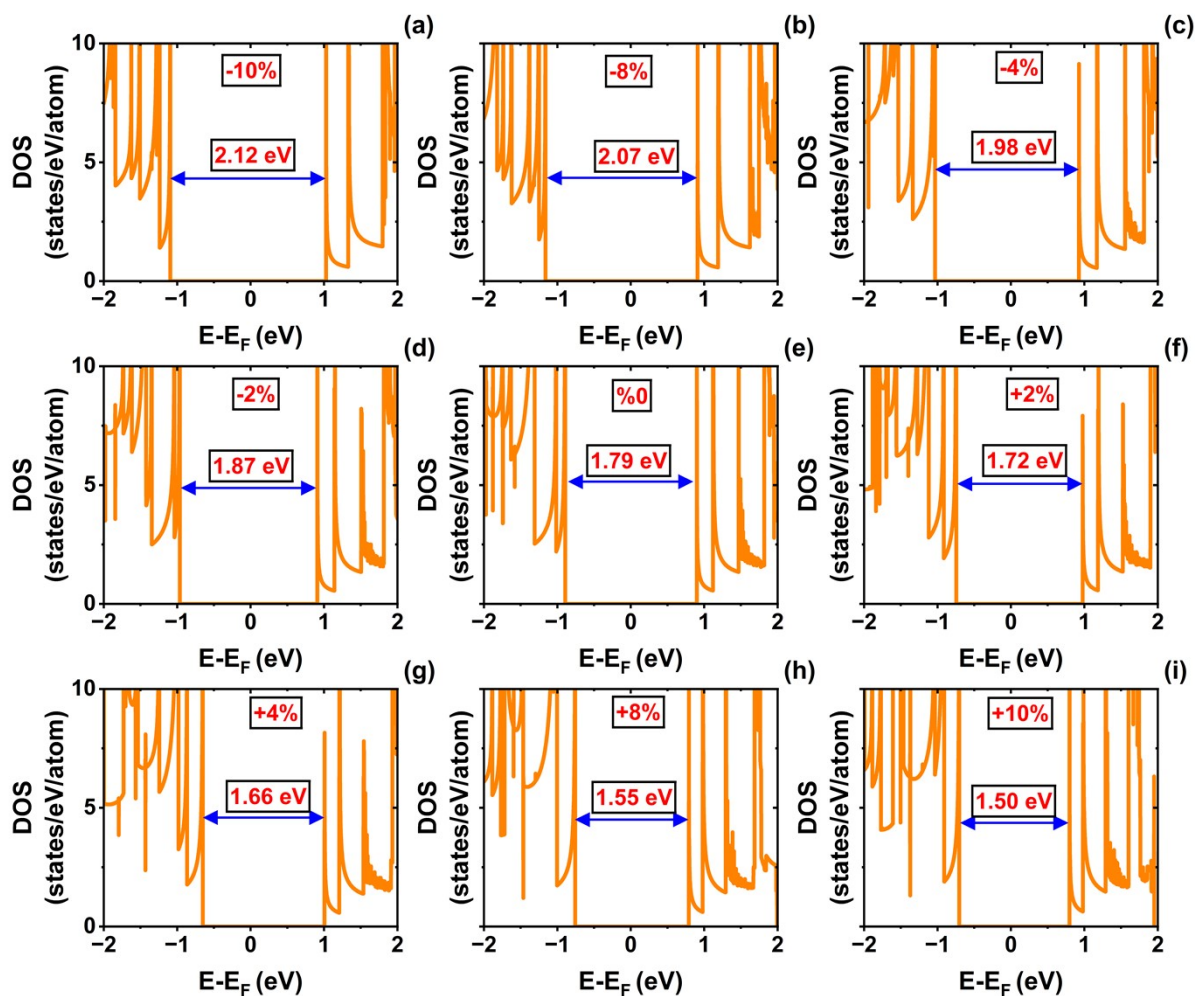


Fig. S5. Density of states (DOS) of the (11,0) single-walled SiCNT under uniaxial strain: (a) –10%, (b) –8%, (c) –4%, (d) –2%, (e) 0% (relaxed state), (f) +2%, (g) +4%, (h) +8%, and (i) +10%.

Figure S6

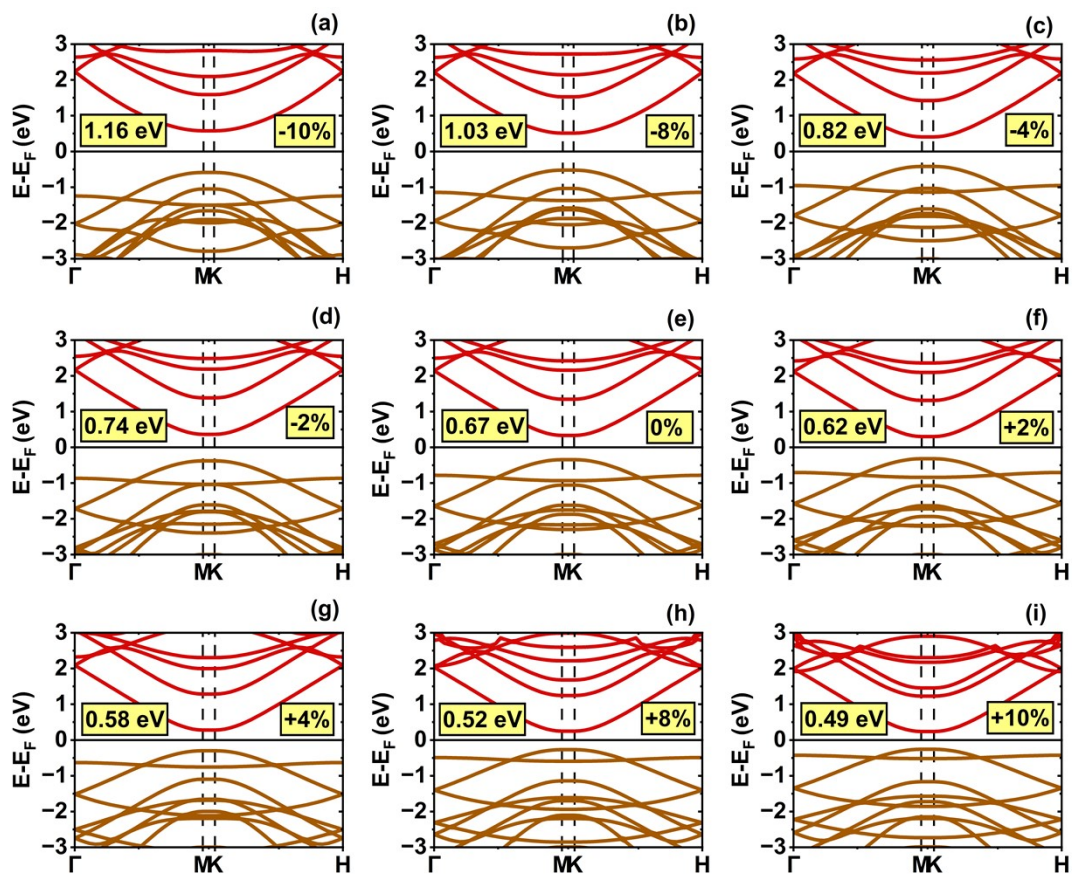


Fig. S6. Electronic band structures of the (6,0) single-walled SiCNT under uniaxial strain: (a) -10% , (b) -8% , (c) -4% , (d) -2% , (e) 0% (relaxed state), (f) $+2\%$, (g) $+4\%$, (h) $+8\%$, and (i) $+10\%$.

Figure S7

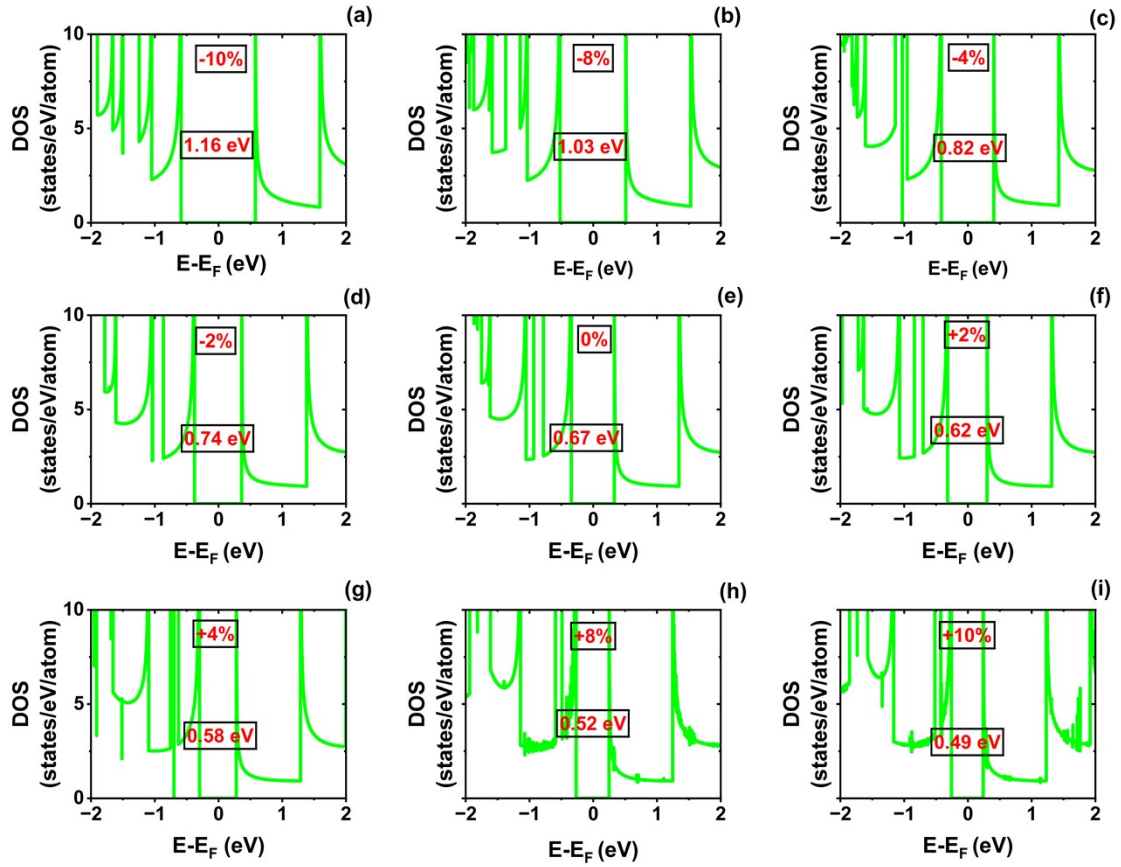


Fig. S7. Density of states (DOS) of the (6,0) single-walled SiCNT under uniaxial strain: (a) –10%, (b) –8%, (c) –4%, (d) –2%, (e) 0% (relaxed state), (f) +2%, (g) +4%, (h) +8%, and (i) +10%.

Figure S8

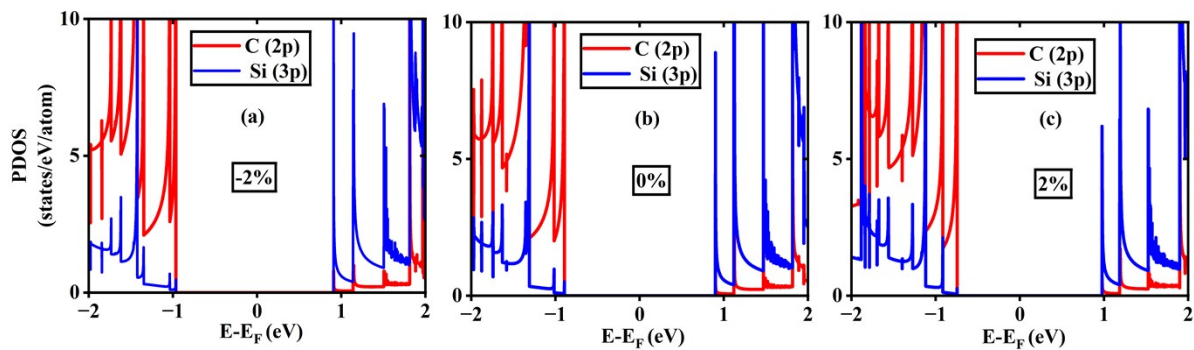


Fig. S8. Orbital-resolved PDOS of the (11,0) SiCNT under (a) -2%, (b) 0%, and (c) +2% strain, highlighting the contributions of C-2p and Si-3p states near the Fermi level.

Table S1. Comparison of bandgap values obtained using different exchange–correlation functionals and thermoelectric parameters of SiCNTs from literature and the present work

(A) Bandgap comparison using different theoretical methods for SWSiCNTs

Nanotube	GGA (present work)	GGA (Literature)	LDA	HSE06(estimated) ¹
(6,0)	0.67 eV	0.68 eV ²	0.70 eV ³	1.70 eV
(10,0)	1.72 eV	1.76 eV ²	1.55 eV ⁴	2.55 eV
(11,0)	1.79 eV	1.87 eV ²	----	----
(6,6)	2.16 eV	2.03 eV ⁵	1.78 eV ⁶	2.78 eV

(B) Thermoelectric parameters from literature (SWCNTs)⁷

Nanotube	Seebeck(μVK^{-1})	σ/τ ($\Omega^{-1} \text{m}^{-1} \text{s}^{-1}$)	PF/ τ ($\text{mW m}^{-1} \text{K}^{-2} \text{s}^{-1}$)
(11,0)	1579 (-3%)	9.75×10^{18} (-3%)	1.55×10^{14} (-9%)
(10,0)	1580 (+3%)	9.5×10^{18} (-9%)	1.44×10^{14} (-3%)
(6,6)	155 (-6%)	2.03×10^{19} (-9%)	2.34×10^{14} (-9%)

(C) Thermoelectric parameters from the present work (SWSiCNTs)

Nanotube	Seebeck(μVK^{-1})	σ/τ ($\Omega^{-1} \text{m}^{-1} \text{s}^{-1}$)	PF/ τ ($\text{mW m}^{-1} \text{K}^{-2} \text{s}^{-1}$)
(11,0)	1550.24 (-10% to +10%)	1.72×10^{19} (-10%)	2.07×10^{14} (-10%)
(10,0)	1550.9 (0%)	1.46×10^{19} (-10%)	1.36×10^{14} (-0% to -2%)
(6,6)	1550 (-10% to +10%)	2.29×10^{19} (-10%)	1.95×10^{14} (+10%)

References

- 1 H. C. Hsueh, G. Y. Guo and S. G. Louie, Excitonic effects in the optical properties of SiC sheet and nanotubes, DOI:10.48550/ARXIV.1105.5531.
- 2 H. Wang, W. Liu and J. Zhao, Theoretical study on the oxidation of zigzag silicon carbide nanotubes (SiCNTs) by singlet O₂, *Phys. B Condens. Matter*, 2012, **407**, 4238–4243.
- 3 I. J. Wu and G. Y. Guo, Optical properties of SiC nanotubes: An *ab initio* study, *Phys. Rev. B*, 2007, **76**, 035343.
- 4 R. J. Baierle, P. Piquini, L. P. Neves and R. H. Miwa, *Ab initio* study of native defects in SiC nanotubes, *Phys. Rev. B*, 2006, **74**, 155425.
- 5 W. Shi, S. Wu and Z. Wang, Tuning the electronic properties of single-walled SiC nanotubes by external electric field, *Phys. E Low-Dimens. Syst. Nanostructures*, 2016, **81**, 192–195.
- 6 Y. Qin, C. Chai, Z. Si, Y. Song and Y. Yang, Six novel silicon carbide with direct bandgaps: A comprehensive study, *Chem. Phys.*, 2022, **561**, 111603.

7Md. M. Islam and A. Zubair, *Ab initio* study of uniaxial strain-induced thermoelectric property tuning of individual single-wall carbon nanotubes, *Mater. Adv.*, 2023, **4**, 6553–6567.